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APPLICATION NO.	FI	LING DATE	FIRST NAMED INVENTOR		ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/648,785	10/648,785 08/27/2003		Joeri Lof		081468-0305473 4480	
909	7590	03/23/2005			EXAMINER	
PILLSBURY WINTHROP, LLP					KO, TONY	
P.O. BOX 10500 MCLEAN, VA 22102					ART UNIT PAPER NUMBER	
-					2878	

DATE MAILED: 03/23/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)	
	10/648,785	LOF ET AL.	
Office Action Summary	Examiner	Art Unit	
	Tony Ko	2878	
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	orrespondence address	
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply If NO period for reply is specified above, the maximum statutory period w - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be time within the statutory minimum of thirty (30) days will apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	nely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).	
Status			
1) Responsive to communication(s) filed on	_•		
	action is non-final.		
3) Since this application is in condition for allowar closed in accordance with the practice under E			
Disposition of Claims			
4) ☐ Claim(s) 1-24 is/are pending in the application. 4a) Of the above claim(s) is/are withdray 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-12 and 17-24 is/are rejected. 7) ☐ Claim(s) 13-16 is/are objected to. 8) ☐ Claim(s) are subject to restriction and/or	vn from consideration.		
Application Papers			
9)☐ The specification is objected to by the Examine 10)☒ The drawing(s) filed on 27 August 2003 is/are: Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11)☐ The oath or declaration is objected to by the Ex	a)⊠ accepted or b)⊡ objected to drawing(s) be held in abeyance. See ion is required if the drawing(s) is ob	e 37 CFR 1.85(a). jected to. See 37 CFR 1.121(d).	
Priority under 35 U.S.C. § 119			
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the priority application from the International Bureau * See the attached detailed Office action for a list	s have been received. s have been received in Applicati rity documents have been receive u (PCT Rule 17.2(a)).	on No ed in this National Stage	
Attachment(s) 1) Notice of References Cited (PTO-892)	4) Interview Summary		
Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date	Paper No(s)/Mail Da 5) Notice of Informal P 6) Other:	ate ratent Application (PTO-152)	

DETAILED ACTION

Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 2. Claims 1, 5, 7, 17, 20, 21-24, are rejected under 35 U.S.C. 102(b) as being anticipated by Moriyama (U.S. Patent 4,798,470).
- alignment tool, comprising: a substrate table (111) configured to hold a substrate having a substrate mark (103), wherein the substrate mark may be at a different level from the rest of the surface of the substrate; and an alignment system (Fig. 11) configured to detect alignment between a reference mark (115) and the substrate mark (103) using an alignment beam of radiation, wherein an optical element (122 or 123) is removably positionable in the path of the alignment beam to adjust the focal plane of the alignment system to focus on the substrate mark at a different level from the rest of the surface of the substrate. Moriyama also discloses the alignment system comprises a projection system (104) and the optical element is placed in the path of the alignment beam directly after the alignment system. Moriyama also discloses a front-to-backside alignment optics configured to direct the alignment beam to the back of the substrate and in which the optical element is placed on the entrance to the front-to-back side alignment optics (Fig. 8). Moriyama also discloses the optical element comprises a

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plurality of optical elements removably positionable in the path of the alignment beam such that one or more (124, 125) may be simultaneously in the path of the alignment beam.

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4. Regarding claims 20 and 21, Moriyama also discloses a lithographic projection apparatus, comprising: a radiation system configured to provide a projection beam of radiation; a support configured to support a patterning device, the patterning device (114) configured to pattern the projection beam according to a desired pattern; a projection system (127) configured to project the patterned beam onto a target portion (102) of a substrate (131); and an alignment tool including a substrate table (111) configured to hold the substrate (131) having a substrate mark (103), wherein the substrate mark (103) may be at a different level from the rest of the surface of the substrate; and an alignment system configured to detect alignment beam of radiation, wherein an optical element is removably positionable in the path of the alignment beam to adjust the focal plane of the alignment system to focus on the substrate mark at a different level from the rest of the surface of the substrate. Moriyama also discloses the alignment beam traverses at least part of the projection system.

Claim Rejections - 35 USC § 103

5. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

⁽a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the

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invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

- 6. Claims 3, 4, 6, 8, 9-12, 18, 19 and 22 are rejected under 35 U.S.C. 103(a) as being unpatentable over Moriyama (U.S. Patent 4,798,470).
- 7. Regarding claim 3, Moriyama discloses the invention set forth above, Moriyama does not disclose to adjust the focal plane of the alignment system by up to 2mm. It is design choice to adjust the focal plane up to 2mm. It would have been obvious to a person of ordinary skill in the art at the time of the invention to adjust the focal plane by up to 2mm to accommodate for different substrate sizes.
- 8. Regarding claim 4, Moriyama discloses the invention set forth above, and Moriyama does not disclose adjust the alignment system by at least 0.1mm. It is design choice to adjust the alignment system by at 0.1mm. It would have been obvious to a person of ordinary skill in the art at the time of the invention to adjust the focal plane by at least 0.1 mm to accommodate for different substrate sizes.
- 9. Regarding claim 6, Moriyama discloses the invention set forth above; Moriyama does not disclose the optical element is attached to the substrate table. It is design choice to attach the optical element to the substrate table. It would have been obvious to a person of ordinary skill in the art at the time of the invention to attach the optical element to the substrate table to ensure the optical element is on the focal point of the alignment beam.
- 10. Regarding claim 8, Moriyama discloses the invention set forth above; Moriyama does not disclose the optical element along the projection beam is altered to adjust the focal plane of the alignment beam. It is well known to adjust the optical element to

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adjust and focus a beam of light. It would have been obvious to a person of ordinary skill in the art at the time of the invention to alter the optical element to adjust the focal plane of an alignment beam to precisely focus the light beam.

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- 11. Regarding claims 18 and 19, Moriyama discloses the invention set forth above, Moriyama does not disclose moving the focal plane of the alignment system in a direction that is perpendicular or parallel to the direction of propagation of the alignment beam. It is well known to adjust the focal plane of the alignment system in a direction that is perpendicular or parallel to the direction of propagation of the alignment to adjust to the different thicknesses of the wafers.
- 12. Claims 2, 9-12 are rejected under 35 U.S.C. 103(a) as being unpatentable over Moriyama (U.S. Patent 4,798,470) in view of Omata (U.S. Patent 4,616,130).
- 13. Regarding claim 2, Moriyama discloses the invention set forth above; Moriyama does not disclose the use of a plane plate. Omata discloses the use of a plane plate (6a). It would have been obvious to a person of ordinary skill in the art at the time of the invention to use a plane plate to achieve the desired refraction angle.
- 14. Regarding claims 9-11, Moriyama discloses the invention set forth above;

 Moriyama does not disclose the optical element comprises a plurality of interchangeable optical elements. Omata discloses (Fig. 1) the optical element comprises a plurality of interchangeable optical elements (6a, 6b) with different thickness (different optical property). It would have been obvious to a person of ordinary skill in the art at the time of the invention to use interchangeable optical elements with different thicknesses for the system to function properly with wafer of different thicknesses.

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15. Regarding claim 12, Moriyama in view of Omata discloses the invention set forth above; Moriyama in view Omata does not disclose to vary the refractive indices. It is well known to vary the refractive indices of the optical elements. It would have been obvious to a person of ordinary skill in the art at the time of the invention to utilize optical elements with different refractive indices to accurately adjust for the different wafers.

Allowable Subject Matter

- **16.** Claims 13-16 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.
- 17. The following is a statement of reasons for the indication of allowable subject matter: Prior art discloses the invention set forth above, prior art does not teach the optical element being hollow and filled with fluid being adjustable to change the refractive index of the optical element.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Tony Ko whose telephone number is 571-272-1926.

The examiner can normally be reached on Monday-Friday 7:30 - 4:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Dave Porta can be reached on 571-272-2444. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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TKO

DAVID PORTA
SOFT - FOR EXAMINER

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